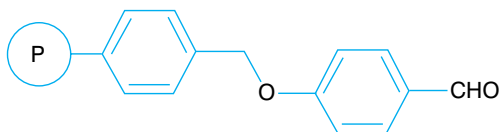


# PL-CHO Resin



## Description

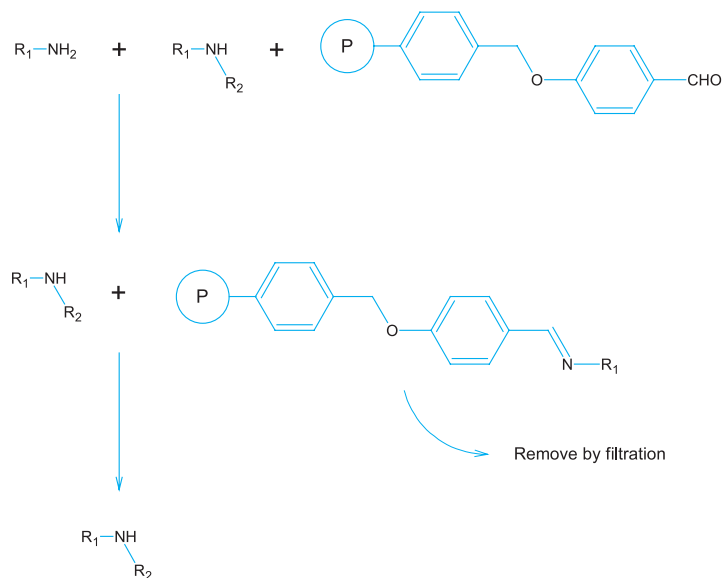
Polymer supported benzaldehyde

## Synonyms

Wang aldehyde resin

## Applications

PL-CHO Resin is designed to remove amines and hydrazines from solution. It is a particularly useful alternative to the highly reactive isocyanate (PL-NCO Resin) and isatoic anhydride (PL-MIA Resin) scavengers, as primary amines can be selectively removed in the presence of secondary amines. It is therefore suitable for removal of unreacted primary amines following a reductive alkylation reaction, for example.



## References

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## Products Information

Microporous

### PL-CHO Resin

3.0mmol/g 150-300 $\mu$ m (50-100 mesh)

Macroporous

### PL-CHO MP-Resin

>1.8mmol/g 100 $\text{\AA}$  150-300 $\mu$ m